

### ABSTRACT OF THE DISCLOSURE

The present invention relates to a matching method of pattern layouts from inverse lithography, which makes the pattern cells in the same groups identical to avoid a repeated verification and to improve the yield. The method comprises the step of: analyzing a target designed layout by hierarchy; categorizing the pattern cells with the same shape into a group; inverting the target designed layout by inverse lithography; inspecting the inversed pattern cells in the group with each other and replacing the variant ones to make all the inversed pattern cells identical.